

AMENDMENT TRANSMITTAL LETTER

Docket No.
0171-1064P

Application No.
10/776,291-Conf. #002846

Filing Date
February 12, 2004

Examiner
J. S. Y. Chu

Art Unit
1752

Applicant(s): Youichi OHSAWA et al.

Invention: NOVEL SULFONYLDIAZOMETHANES, PHOTOACID GENERATORS, RESIST COMPOSITIONS, AND PATTERNING PROCESS

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Transmitted herewith is an amendment in the above-identified application.

The fee has been calculated and is transmitted as shown below.

CLAIMS AS AMENDED					
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present	Rate	
Total Claims	15	- 20 =		x	
Independent Claims	2	- 3 =		x	
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>					
Other fee (please specify): Extension for response within first month					120.00
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT:					120.00

☒ Large Entity

☐ Small Entity

☐ No additional fee is required for this amendment.

☐ Please charge Deposit Account No. _____ in the amount of \$ _____.
A duplicate copy of this sheet is enclosed.

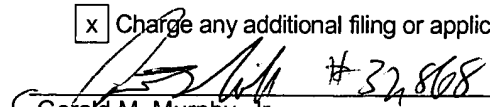
☒ A check in the amount of \$ 120.00 to cover the filing fee is enclosed.

☐ Payment by credit card. Form PTO-2038 is attached.

☒ The Director is hereby authorized to charge and credit Deposit Account No. 02-2448
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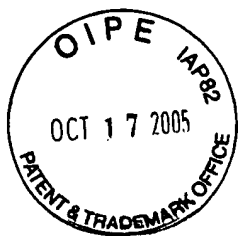
☒ Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.

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Dated: October 17, 2005

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Docket No.: 0171-1064P
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Youichi OHSAWA et al.

Application No.: 10/776,291

Confirmation No.: 002846

Filed: February 12, 2004

Art Unit: 1752

For: NOVEL SULFONYLDIAZOMETHANES,
PHOTOACID GENERATORS, RESIST
COMPOSITIONS, AND PATTERNING
PROCESS

Examiner: J. S. Y. Chu

AMENDMENT IN RESPONSE TO NON-FINAL OFFICE ACTION

MS Amendment
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P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

INTRODUCTORY COMMENTS

In response to the Office Action dated June 16, 2005, please amend the above-identified U.S. patent application as follows:

Remarks/Arguments begin on page 2 of this paper.